

# Semiconductor Materials

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# 演習1

## Exercise1

アセプター濃度  $N_A = 1 \times 10^{19} / \text{cm}^3$  の p-Si と

ドナー濃度  $N_D = 1 \times 10^{16} / \text{cm}^3$  の n-Si

の pn 接合における内蔵電位を求めよ。  
(300K).

$$E_g = E_c - E_v = 1.1 \text{ eV}$$

$$N_c = 2.86 \times 10^{19} / \text{cm}^3$$

$$N_v = 2.66 \times 10^{19} / \text{cm}^3$$

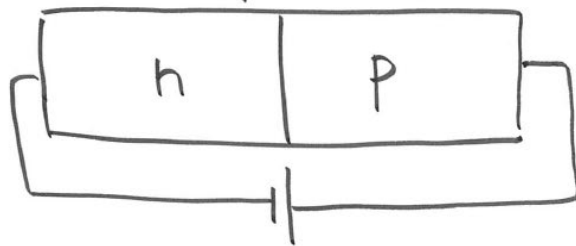
$$kT = 0.026 \text{ eV}$$

$$q = 1.6 \times 10^{-19} \text{ C}$$

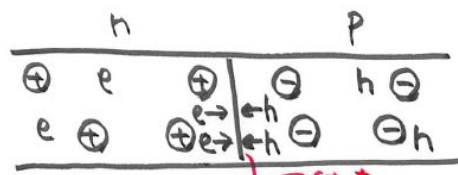
Evaluate the built-in potential for the pn junction where the acceptor density and donor density in Si are  $N_A = 1 \times 10^{19} \text{ cm}^{-3}$  and  $N_D = 1 \times 10^{16} \text{ cm}^{-3}$ , respectively.

pn 接合 pn junction

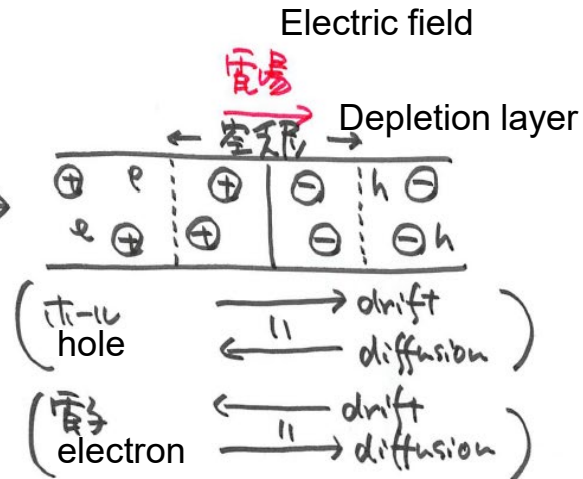
整流作用 Rectifying effect

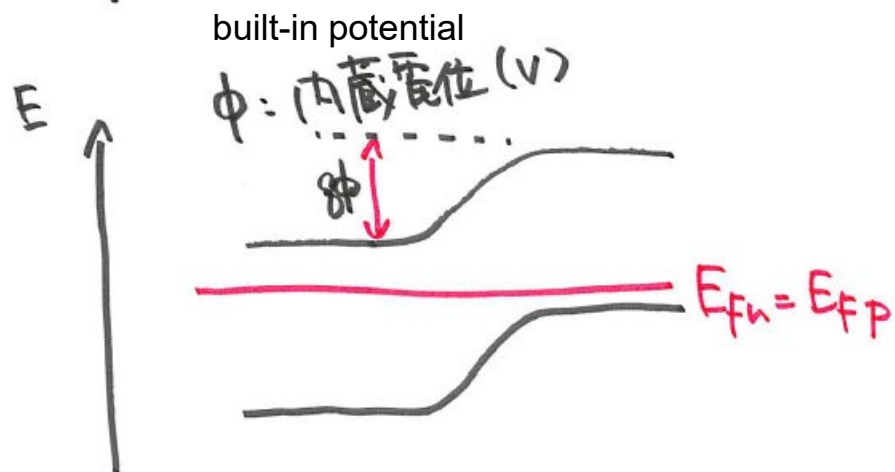
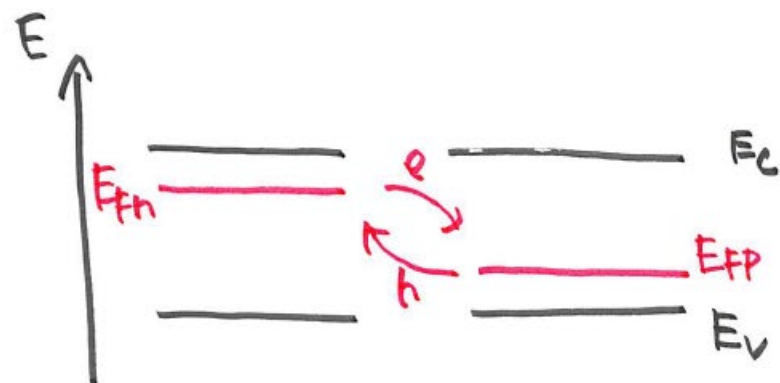


ダイオード, LED (Light Emitting Diode)



再結合 recombination  
拡散 diffusion

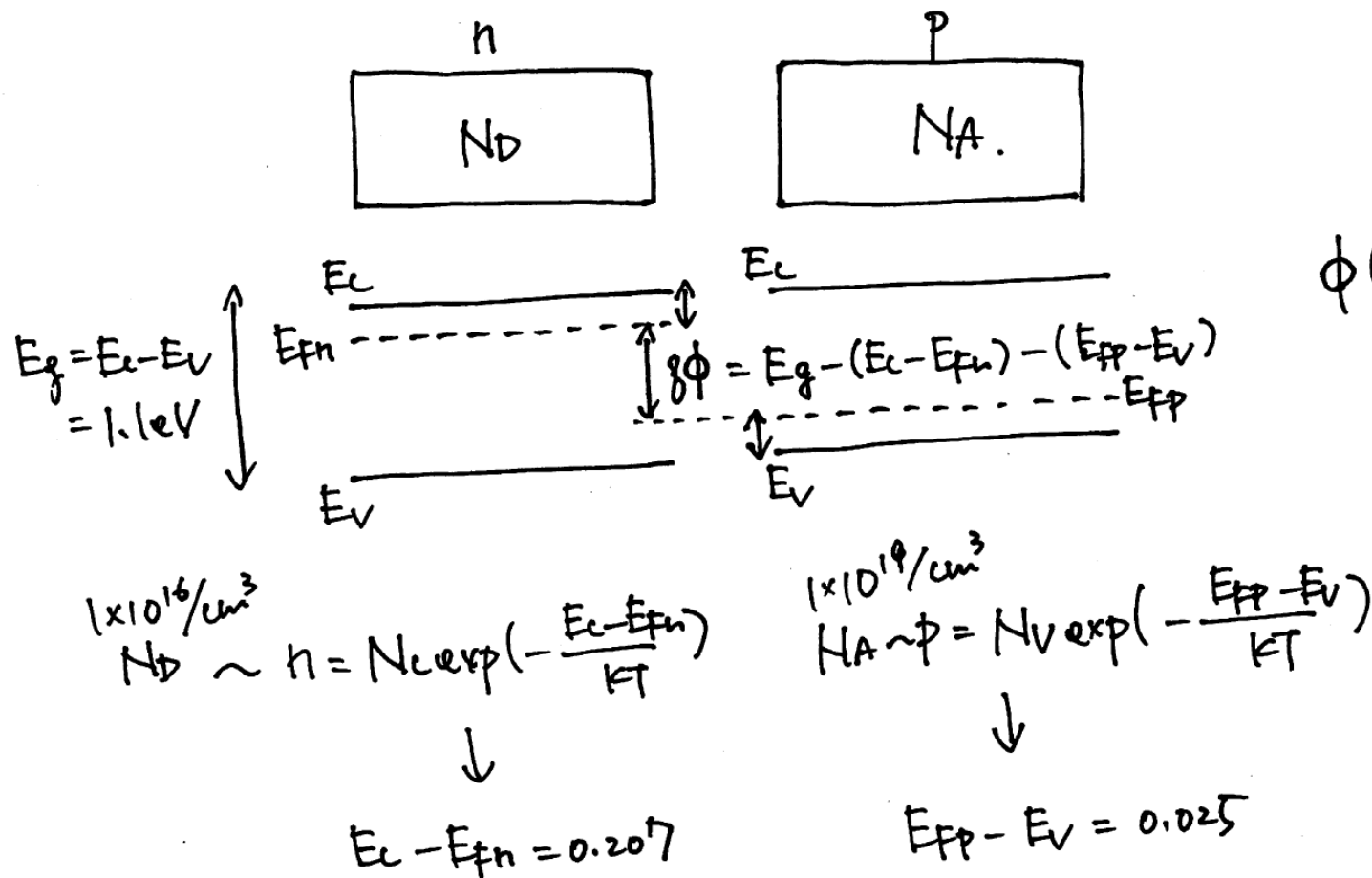




→ 電場

Electric field

演習1  
Exercise1  
(solution)



内蔵電位  
 $\phi(V) = \text{built-in potential.}$

$$q\phi = 0.87 \text{ (eV)} = 0.87 \times q \text{ (J)}. \quad \text{電荷量 (elementary charge)}$$

$$\therefore \phi = \frac{0.87 \times q \text{ (J)}}{q \text{ (C)}} = 0.87 \text{ (V)}.$$

eV

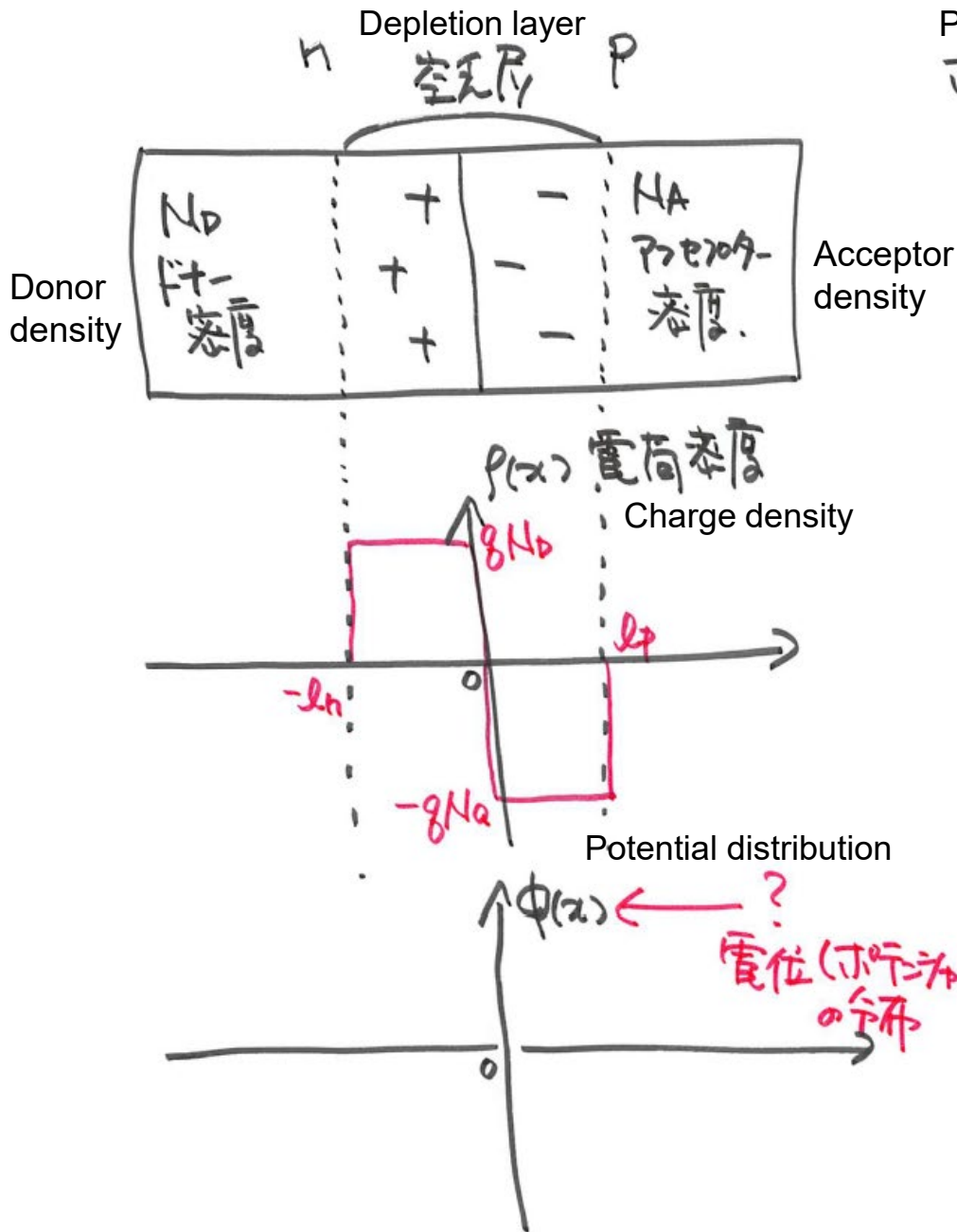
1eV:  $+q \text{ (C)}$  の電荷を 1(V) だけ電位の  
高  $\therefore E = qV$  運ぶのに必要な仕事

Energy necessary to carry a  
particle  $(+q)$  to a position  
where the position is 1(V) higher.



$$1\text{eV} = q \text{ (C)} \times 1 \text{ (V)} \\ = 1.6 \times 10^{-19} \text{ (J)}.$$





Poisson's equation  
ポアソン方程式

$$\frac{d^2\phi(x)}{dx^2} = -\frac{\rho(x)}{\epsilon_s}$$

Permittivity of Si  
Siの誘電率

relative permittivity of Si  
Siの相対誘電率

Permittivity of vacuum  
真空の誘電率

$11.7 \times 8.854 \times 10^{-12} \text{ F/m}$

$\rho(x) \rightarrow \phi(x)$  電荷密度から電位の方程式

Differential equation

境界条件  
Boundary condition

$$E(-l_n) = E(l_p) = 0$$

$$\phi(0) = 0$$

中性条件  
Neutral condition

$$N_D l_n = N_A l_p$$



$$(i) \quad 0 \leq x \leq l_p, \quad \rho(x) = -gNA$$

$$\frac{d^2\phi(x)}{dx^2} = \frac{gNA}{\epsilon_s}$$

↓

$$-E(x) = \frac{d\phi(x)}{dx} = \frac{gNA}{\epsilon_s} x + A = \frac{gNA}{\epsilon_s} (x - l_p)$$

↓

Electric field  
電場

$$\phi(x) = \frac{gNA}{\epsilon_s} \frac{(x - l_p)^2}{2} + B = \frac{gNA}{2\epsilon_s} \{ (x - l_p)^2 - l_p^2 \}$$

↑

$\phi(0) = 0$

$$(ii) \quad -l_n \leq x \leq 0, \quad \rho(x) = gNd$$

$$\phi(x) = -\frac{gNd}{2\epsilon_s} \{ (x + l_n)^2 - l_n^2 \}$$

$$-l_n \leq x \leq 0 \quad n \in \mathbb{I}. \quad \rho(x) = \rho_{n0}$$

$$\frac{d^2 \phi(x)}{dx^2} = -\frac{\rho_{n0}}{\epsilon_s}$$

↓

$$-E(x) = \frac{d\phi(x)}{dx} = -\frac{\rho_{n0}}{\epsilon_s} x + A = -\frac{\rho_{n0}}{\epsilon_s} (x + l_n)$$

$$E(-l_n) = 0.$$

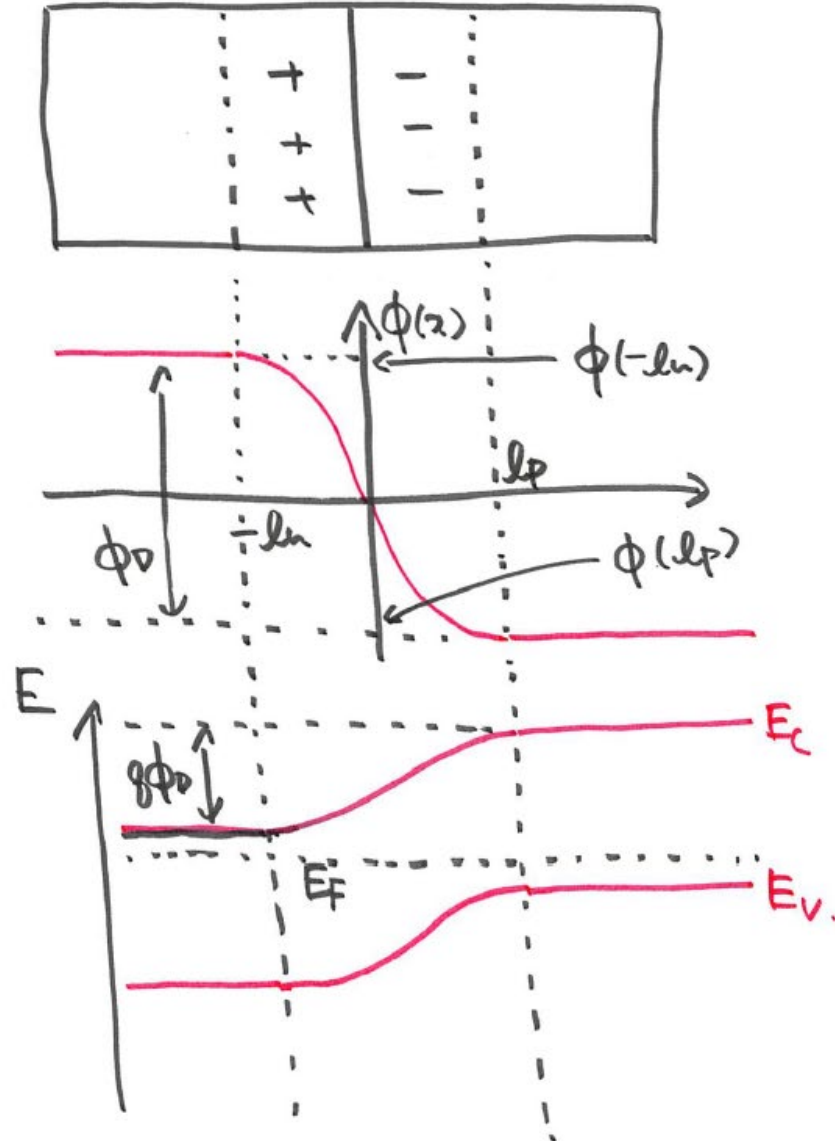
↓

$$\phi(x) = -\frac{\rho_{n0}}{\epsilon_s} \frac{(x + l_n)^2}{2} + B = -\frac{\rho_{n0}}{2\epsilon_s} \left\{ (x + l_n)^2 - l_n^2 \right\}.$$

$$\phi(0) = 0$$

Built-in potential

内蔵電位



$$\phi_0 = \phi(-ln) - \phi(lnp)$$

$$= -\frac{qN_D}{2\epsilon_s} ln^2 + \frac{qN_A}{2\epsilon_s} l_p^2$$

# Derivation of depletion layer width

## 空乏層幅の導出

$$\begin{aligned}\phi_D &= -\frac{q}{2\epsilon_s} (N_D l_n^2 + N_A l_p^2) \\ &= -\frac{q}{2\epsilon_s} (N_D l_n^2 + \underbrace{(N_A l_p)}_{N_D l_n} l_p) \quad N_D l_n \\ &= -\frac{q}{2\epsilon_s} \underbrace{N_D l_n}_{\substack{\uparrow \\ W \text{ (空乏層の中)}}} (\underbrace{l_n + l_p}_W) \end{aligned}$$

$$\begin{cases} l_n + l_p = W \\ N_D l_n = N_A l_p \end{cases}$$

↓

$$l_n = \frac{N_A}{N_A + N_D} W$$

$$W = l_n + l_p$$

$$= \sqrt{\frac{2\epsilon_s}{q} \cdot \frac{N_A + N_D}{N_A N_D} \phi_D}$$

## 演習

## Exercise

$N_A = 1 \times 10^{19} / \text{cm}^3$ ,  $N_D = 1 \times 10^{16} / \text{cm}^3$  のとき、

空乏層の中  $x=0$  での電場  $E(0)$  を求めよ。

Derive the depletion layer width and electric field at the junction,  $E(0)$ , for the pn junction where the acceptor density and donor density in Si are  $N_A = 1 \times 10^{19} \text{ cm}^{-3}$  and  $N_D = 1 \times 10^{16} \text{ cm}^{-3}$ , respectively.

$$q = 1.6 \times 10^{-19} (\text{C}), \quad \epsilon_s = 11.7 \times 8.854 \times 10^{-12} (\text{F/m})$$